

[METHOD OF MANUFACTURING COLOR FILTER ARRAY AND THIN FILM]

Abstract

A method of manufacturing a color filter array is provided. The manufacturing method is as follows. Step (a), form a patterned first photoresist layer over a substrate. The patterned first photoresist layer has a plurality of openings that exposes a portion of the substrate. Step (b), form a filter material layer on the exposed area of the substrate. Step (c), form a second photoresist layer on the filter material layer. Step (d), remove the first and the second photoresist layer such that the filter material layer forms a plurality of first filter films. Step (e), repeat step (a) to (c) at least once and remove the first and the second photoresist layer to form a plurality of second filter films in areas except the first color filter films. The aforementioned method of forming the color filter array can form filter films having perpendicular sidewalls on the substrate.